DISCUSSION OF THE AMENDMENT

Claims 1 and 16-21 have been canceled.

Claims 2 and 3 have each been amended by deleting the limitation that at least one of the first inorganic compound layer and the second inorganic compound layer having been subjected to crystallization treatment, and by inserting that the second inorganic compound layer being able to be etched more easily than the first inorganic compound layer, as supported in the specification at paragraphs [0038] and [0039].

Claims 7 and 23 have been amended to depend on Claims 2 and 3, respectively.

New Claims 30 and 31 have been added, as supported in the specification at paragraphs [0043] and [0045].

No new matter is believed to have been added by the above amendment. Claims 2, 3, 6-11, 13, 15, and 22-31 are now pending in the application.

REMARKS

The rejection of Claims 1-3, 6-11, 13 and 15-29 under 35 U.S.C. § 103(a) as unpatentable over US 7,030,553 (Winters et al) in view of US 2003/0184688 (Kim), is respectfully traversed.

The present invention is drawn to an organic EL display containing two (Claim 2 and claims dependent thereon) or three (Claim 3 and claims dependent thereon) organic EL device parts wherein an inorganic compound layer (for adjusting the optical thickness of a resonator of the organic EL device part) **comprises a first compound layer and a second compound layer, and the second inorganic compound layer can be etched more easily than the first inorganic compound layer**. The features enable the efficient formation of inorganic compound layers having different thicknesses in devices, by sputtering of a first inorganic compound layer (Fig. 5(c)), photolithography, etching (Fig. 5(d)), crystallization, sputtering of a second inorganic compound layer (Fig. 5(e)), photolithography, and etching (Fig. 5(f)), as shown in Fig. 5. In device parts, an organic luminescent medium layer, light reflective layer and transparent electrode layer can be formed as the same common films thereon. Thus the production steps can be simplified, which is extremely advantageous in industrial production.

Winters et al discloses inorganic compound layers with different thicknesses in devices but the layers are formed by deposition. When layers 140a and 140b, which are different in thickness, are formed by deposition in only pixels 21a and 21b of pixels 21a, 21b and 21c as shown in Fig. 2 therein, two mask deposition steps are generally required. However, when the mask deposition is conducted in vacuum, it is difficult to control positioning and the like. Thus the mask deposition does not result in excellent productivity.

In contrast, according to the present invention, inorganic compound layers with different thicknesses in devices can be formed without using the mask deposition in vacuum.

Thus the present invention does not suffer from the above control difficulty and is excellent in productivity.

As stated above, the present invention is excellent in productivity compared to Winters et al and is not suggested by Winters et al.

Kim discloses selective etching in the formation of LCD pixels. Kim is characterized by simplifying the production of an electrode. The prior art requires complicated and time consuming steps such as depositing, exposing, developing, etching, stripping and cleaning, as described therein at paragraphs [0025] to [0027]. Specifically, after forming an ITO layer, a part thereof is crystallized by light irradiation and a non-crystallized part is removed.

While Kim thus discloses sputtering, photolithography and etching, Kim discloses only the patterning of a single layer of an electrode. Kim neither discloses nor suggests how to efficiently form inorganic compound layers having different thicknesses in devices for adjusting the optical thickness of a resonator of an organic EL device part. While, as the Examiner finds, Kim discloses an amorphous material having a higher etching rate than a crystalline material, nevertheless, without the present disclosure as a guide, one of ordinary skill in the art would not have combined Winters et al and Kim. But even if combined, the result would be only patterning of a single layer constituting an organic EL device by selective etching.

For all the above reasons, it is respectfully requested that this rejection be withdrawn.

All of the presently-pending claims in this application are now believed to be in immediate condition for allowance. Accordingly, the Examiner is respectfully requested to pass this application to issue.

Respectfully submitted,

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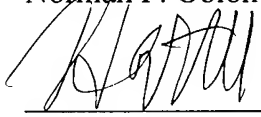

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